

Amendments to the Claims

1. (Currently Amended): An Aboron and/or phosphorus doped silicon dioxide selective to undoped  $\text{SiO}_2$  and  $\text{Si}_3\text{N}_4$  etchant gas composition, comprising:

a carrier gas;

$\text{C}_4\text{F}_6$ ; at least one of  $\text{C}_4\text{F}_6$ ,  $\text{C}_3\text{F}_6$  and  $\text{C}_5\text{F}_8$ ;

$\text{CH}_2\text{F}_2$ ; and

a gas selected from the group consisting of  $\text{CHF}_3$ ,  $\text{CF}_4$ , and mixtures thereof.

C 1  
Claims 2 and 3 (Previously Canceled).

4. (Original): The etchant gas composition according to Claim 1, wherein the carrier gas is selected from the group consisting of argon, helium, and xenon.

5. (Previously Amended): The etchant gas composition according to Claim 1, wherein the carrier gas comprises argon.

6. (Currently Amended): An A boron and/or phosphorus doped silicon dioxide selective to undoped SiO<sub>2</sub> and Si<sub>3</sub>N<sub>4</sub> etchant gas composition, consisting essentially of:

a carrier gas;

C<sub>4</sub>F<sub>6</sub>; at least one of C<sub>4</sub>F<sub>6</sub>, C<sub>3</sub>F<sub>6</sub> and C<sub>5</sub>F<sub>8</sub>;

CH<sub>2</sub>F<sub>2</sub>; and

CHF<sub>3</sub>.

Claims 7 and 8 (Previously Canceled).

9. (Original): The etchant gas composition according to Claim 6, wherein the carrier gas is selected from the group consisting of argon, helium, and xenon.

10. (Previously Amended): The etchant gas composition according to Claim 6, wherein the carrier gas comprises argon.

11. (Currently Amended): An A boron and/or phosphorus doped silicon dioxide selective to undoped SiO<sub>2</sub> and Si<sub>3</sub>N<sub>4</sub> etchant gas composition, consisting essentially of:

a carrier gas;

C<sub>4</sub>F<sub>6</sub>; at least one of C<sub>4</sub>F<sub>6</sub>, C<sub>3</sub>F<sub>6</sub> and C<sub>5</sub>F<sub>8</sub>;

CH<sub>2</sub>F<sub>2</sub>; and

CF<sub>4</sub>.

C1  
Claims 12 and 13 (Previously Canceled).

14. (Original): The etchant gas composition according to Claim 11, wherein the carrier gas is selected from the group consisting of argon, helium, and xenon.

15. (Previously Amended): The etchant gas composition according to Claim 11, wherein the carrier gas comprises argon.

16. (Currently Amended): An A boron and/or phosphorus doped silicon dioxide selective to undoped SiO<sub>2</sub> and Si<sub>3</sub>N<sub>4</sub> etchant gas composition, consisting essentially of:

a carrier gas;

C<sub>4</sub>F<sub>6</sub>; at least one of C<sub>4</sub>F<sub>6</sub>, C<sub>3</sub>F<sub>6</sub> and C<sub>5</sub>F<sub>8</sub>;

CH<sub>2</sub>F<sub>2</sub>;

CHF<sub>3</sub>; and

CF<sub>4</sub>.

(1)

Claims 17 and 18 (Previously Canceled).

19. (Original): The etchant gas composition according to Claim 6, wherein the carrier gas is selected from the group consisting of argon, helium, and xenon.

20. (Previously Amended): The etchant gas composition according to Claim 16, wherein the carrier gas comprises argon.

Claims 21-64 (Previously Canceled).

65. (Previously Added): The etchant gas composition according to  
Claim 1 comprising O<sub>2</sub>.

66. (Previously Added): The etchant gas composition according to  
Claim 1 comprising CO.

67. (Previously Added): The etchant gas composition according to  
Claim 1 wherein the carrier gas comprises helium.

68. (Previously Added): The etchant gas composition according to  
Claim 6 wherein the carrier gas comprises helium.

69. (Previously Added): The etchant gas composition according to  
Claim 11 wherein the carrier gas comprises helium.

70. (Previously Added): The etchant gas composition according to  
Claim 16 wherein the carrier gas comprises helium.

71. (Previously Added): The etchant gas composition according to  
Claim 1 wherein the carrier gas comprises xenon.

72. (Previously Added): The etchant gas composition according to  
Claim 6 wherein the carrier gas comprises xenon.

73. (Previously Added): The etchant gas composition according to Claim 11 wherein the carrier gas comprises xenon.

74. (Previously Added): The etchant gas composition according to Claim 16 wherein the carrier gas comprises xenon.

75. (New): The etchant gas composition according to Claim 1, comprising  $C_4F_6$ .

76. (New): The etchant gas composition according to Claim 1, comprising  $C_3F_6$ .

77. (New): The etchant gas composition according to Claim 1, comprising  $C_5F_8$ .

78. (New): The etchant gas composition according to Claim 6, comprising  $C_4F_6$ .

79. (New): The etchant gas composition according to Claim 6, comprising  $C_3F_6$ .

80. (New): The etchant gas composition according to Claim 6, comprising  $C_5F_8$ .

81. (New): The etchant gas composition according to Claim 11, comprising C<sub>4</sub>F<sub>6</sub>.

82. (New): The etchant gas composition according to Claim 11, comprising C<sub>3</sub>F<sub>6</sub>.

83. (New): The etchant gas composition according to Claim 11, comprising C<sub>5</sub>F<sub>8</sub>.

84. (New): The etchant gas composition according to Claim 16, comprising C<sub>4</sub>F<sub>6</sub>.

85. (New): The etchant gas composition according to Claim 16, comprising C<sub>3</sub>F<sub>6</sub>.

86. (New): The etchant gas composition according to Claim 16, comprising C<sub>5</sub>F<sub>8</sub>.